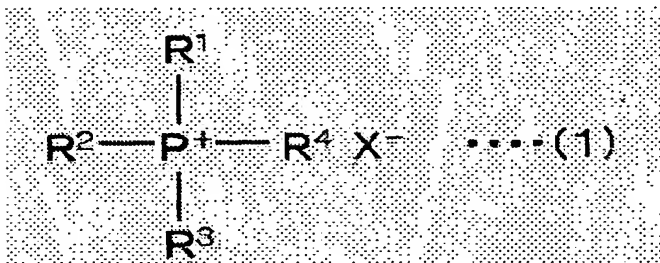


## CLAIMS

1. An antistatic agent for resins, containing phosphonium salts represented by the general formula (1):



5 (wherein  $\text{R}^1$ ,  $\text{R}^2$ , and  $\text{R}^3$  are each a straight-chain or branched alkyl group having 3 to 8 carbon atoms, and  $\text{R}^4$  is a straight-chain or branched alkyl group having 10 to 22 carbon atoms; each alkyl group may have substituted hydroxy group or alkoxy group;  $\text{R}^1$ ,  $\text{R}^2$ , and  $\text{R}^3$  may be the same or different from each another; and  $\text{X}^-$  is a tetrafluoroborate ion or  
10 a hexafluorophosphate ion).

2. The antistatic agent for resins according to Claim 1, wherein the phosphonium salt is tri-n-butyl-n-hexadecylphosphonium tetrafluoroborate.

3. The antistatic agent for resins according to Claim 1,  
15 wherein the phosphonium salt is tri-n-butyl-n-hexadecylphosphonium hexafluorophosphate.

4. The antistatic agent for resins according to any of Claims 1 to 3, wherein the residual halogen is 500 ppm or less.

5. The antistatic agent for resins according to any of Claims  
20 1 to 4, wherein the antistatic agent is for thermoplastic resins.

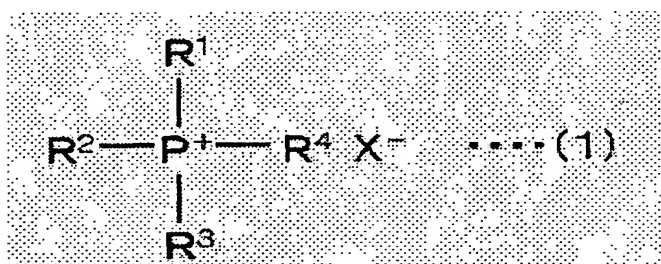
6. The antistatic agent for resins according to Claim 5, wherein the antistatic agent is for polyamide resins or for polyester

resins.

7. The antistatic agent for resins according to any of Claims 1 to 4, wherein the antistatic agent is for thermoset resins.

8. The antistatic agent for resins according to Claim 7, wherein the antistatic agent is for polyurethane resins or for epoxy resins.

9. An antistatic resin composition, containing a resin and phosphonium salts represented by the general formula (1):



10 (wherein  $\text{R}^1$ ,  $\text{R}^2$ , and  $\text{R}^3$  are each a straight-chain or branched alkyl group having 3 to 8 carbon atoms, and  $\text{R}^4$  is a straight-chain or branched alkyl group having 10 to 22 carbon atoms; each alkyl group may have substituted hydroxy group or alkoxy group;  $\text{R}^1$ ,  $\text{R}^2$ , and  $\text{R}^3$  may be the same or different from each another; and  $\text{X}^-$  is a tetrafluoroborate ion or a hexafluorophosphate ion).

10. The antistatic resin composition according to Claim 9, wherein the phosphonium salt is tri-n-butyl-n-hexadecylphosphonium tetrafluoroborate.

11. The antistatic resin composition according to Claim 9, wherein the phosphonium salt is tri-n-butyl-n-hexadecylphosphonium hexafluorophosphate.

12. The antistatic resin composition according to any of

Claims 9 to 11, wherein the amount of the phosphonium salt compounded is 0.01 to 50 weight parts per 100 weight parts resin.

13. The antistatic resin composition according to any of Claims 9 to 12, wherein the resin is a thermoplastic resin.

5           14. The antistatic resin composition according to Claim 13, wherein the thermoplastic resin is a polyamide or a polyester.

15. The antistatic resin composition according to any of Claims 9 to 12, wherein the resin is a thermoset resin.

10           16. The antistatic resin composition according to Claim 15, wherein the thermoset resin is polyurethane resin or epoxy resin.

17. The antistatic resin composition according to any of Claims 9 to 16, wherein carbon material is further contained.

18. The antistatic resin composition according to Claim 17, wherein the carbon nanotubes are contained as the carbon material.

15           19. An antistatic resin molded product, wherein the antistatic resin composition of any of Claims 9 to 18 is molded.